

FORM PTO-1449				U.S. Department of Commerce Patent and Trademark Office		Atty. Docket No. P25051	Application No. 10/814,252		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)				Applicant István Endre LAUKÁCS et al					
				Filing Date April 1, 2004		Group 2877			
U.S. PATENT DOCUMENTS									
EXAMINER INITIAL	DOCUMENT NUMBER				DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SN	4	5	4	7	0	7	3	10/15/85	KUGIMIYA
FOREIGN PATENT DOCUMENTS									
	DOCUMENT NUMBER				DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
SN	0	2	/	2	9	8	3	5	05/25/00 W.I.P.O
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)									
SN	1	Yang, "An Optical Imaging Method for Wafer Warpage Measurements," <i>Journal of the Electrochemical Society</i> , Vol. 132, No. 5, pp. 1214 – 1218 (1985).							
↑	2	"Optical Shop Testing," ed. Malacara, John Wiley & Sons, New York pp. 323 – 349 (1979).							
	3	Riesz, "Geometrical Optical Model of the Image Formation in Makyoh (Magic Mirror) Topography," <i>J.Phys.D: Appl.Phys.</i> , Vol. 33, pp. 3033 – 3040, XP002229672 UK (2000).							
	4	Riesz, "Camera Length and Field of View in Makyoh-topography Instruments," R.S.I., Vol. 72, No. 2, PP. 1591 – 1593, XP002229673 America (February 2001 (2001 – 02)).							
	5	Reisz, "Makyoh Topography for the Morphological Study of Compound Semiconductor Wafer and Structures," <i>Material Science & Engineering</i> , Vol. B80, pp. 220 – 223, XP002229676 NL (2001).							
	6	Szabo et al., "Makyoh Topography: Curvature Measurements and Implications for the Image Formation," <i>Jpn. J. Appl. Phys.</i> , Vol. 35, pp. L258 – L261, XP002229674 (February 15, 1999).							
	7	Laczik, "Quantitative Makyoh Topography," <i>Proc. Annual ACM Symp. On Principles of Distributed Computing</i> , Vol. 3743, pp. 151 – 156, XP000874538 (May 1999).							
	8	Török et al., "Applications of Scanning Optical Microscopy in Materials Science to Detect Bulk Microdefects in Semiconductors," <i>Journal of Microscopy</i> , Vol. 188, No. 1, pp. 1 – 16, XP002229675 UK (October 1997).							
	9	Koehler, "Plane-wave X-ray Topography and its Application to Semiconductor Problems," <i>Journal of Materials Science, Material in Electronics</i> , Chapman and Hall, London GB, pp. 167 – 174, XP000912483, ISSN: 0957-4522 (May 3, 1999).							
↓	1	0	Kayaalp et al., "Using SEM Stereo to Extract Semiconductor Wafer Pattern Topography," <i>Proceedings of the SPIE</i> , SPIE, Bellingham VA, US, vol. 775, pp. 18 – 26, XP000918713 (1987).						
EXAMINER <i>Sanghyun</i>				DATE CONSIDERED <i>1/25/05</i>					
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.									